

# Physically-Based Compact Modeling for Amorphous Oxide Thin Film Transistors

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## Introduction

- Both TLC, associated with tails states, and Percolation, due to compositional disorder, considered.
- Above-threshold and Sub-threshold models separately derived and combined in a harmonic average.

## Results and Discussions

- Mobility and I-V relation for above-threshold regime:

$$\mu_0^* = \mu_0 \exp\left(\frac{-q\phi_{B0}}{kT} + \frac{(q\sigma_{B0})^2}{2(kT)^2}\right)$$

$$\mu_n = \mu_0 \exp\left(\frac{-q\phi_{B0}}{kT} + \frac{(q\sigma_{B0})^2}{2(kT)^2}\right) \exp\left(\frac{\gamma_B}{kT}(E_F - E_m)\right)$$

$$\mu_{FE}(V_{GS}, V_{ch}) \approx \mu_0^* \left(\frac{N_C}{N_C + 0.5N_{tc}kT_i}\right) \left(\frac{C_{ox}}{Q_{ref}}\right)^{\alpha_p} (V_{GS} - V_{ch} - V_T)^{\alpha_p}$$

$$I_{DS} \approx \mu_{FE} \left(\frac{N_C}{N_C + 0.5N_{tc}kT_i}\right) WC_{ox}(V_{GS} - V_{ch} - V_T) \frac{dV_{ch}}{dx}$$

$$\int_0^L I_{DS} dx \approx \mu_0^* \left(\frac{N_C}{N_C + 0.5N_{tc}kT_i}\right) W \frac{C_{ox}^{\alpha_p+1}}{Q_{ref}^{\alpha_p}} \int_0^{V_{DS}} (V_{GS} - V_{ch} - V_T)^{\alpha_p+1} dV_{ch}$$

$$I_{DS} = \mu_0^* \left(\frac{N_C}{N_C + 0.5N_{tc}kT_i}\right) \frac{W}{L} \frac{C_{ox}^{\alpha_p+1}}{Q_{ref}^{\alpha_p} (\alpha_p + 2)} \left[ (V_{GS} - V_T)^{\alpha_p+2} - (V_{GS} - V_T - V'_{DS})^{\alpha_p+2} \right]$$

$$(V_{GS} - V_T)^{\alpha_p+2} - (V_{GS} - V_T - V'_{DS})^{\alpha_p+2} \approx (\alpha_p + 2)(V_{GS} - V_T)^{\alpha_p+1} V'_{DS}$$

$$I_{sat} = \mu_0^* \left(\frac{N_C}{N_C + 0.5N_{tc}kT_i}\right) \frac{W}{L} \frac{C_{ox}^{\alpha_p+1}}{Q_{ref}^{\alpha_p}} (V_{GS} - V_T)^{\alpha_p+2} \alpha_{sat}$$

- Sub-threshold equations based on drift and diffusion:

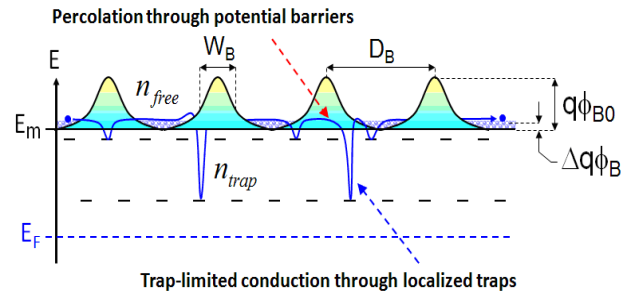
$$I_{Diff} \approx \mu_0 \frac{kT}{q} \frac{W}{L} Q_{ref} \exp\left(\frac{q}{kT} \left( \frac{V_{GS} - V_{FB}}{1 + q^2 D_u / C_{ox}} \right) \right) \left( 1 - \exp\left(-\frac{qV'_{DS}}{kT}\right) \right)$$

$$I_{Drift} \approx \mu_0 \frac{W}{L} \frac{C_{ox}^{\alpha_p+1}}{Q_d^{\alpha_p}} (V_{GS} - V_{FB})^{\alpha_p+2} \beta_{sat} \quad I_{sub} \equiv (I_{Diff}^m + I_{Drift}^m)^{-1/m}$$

## Conclusion

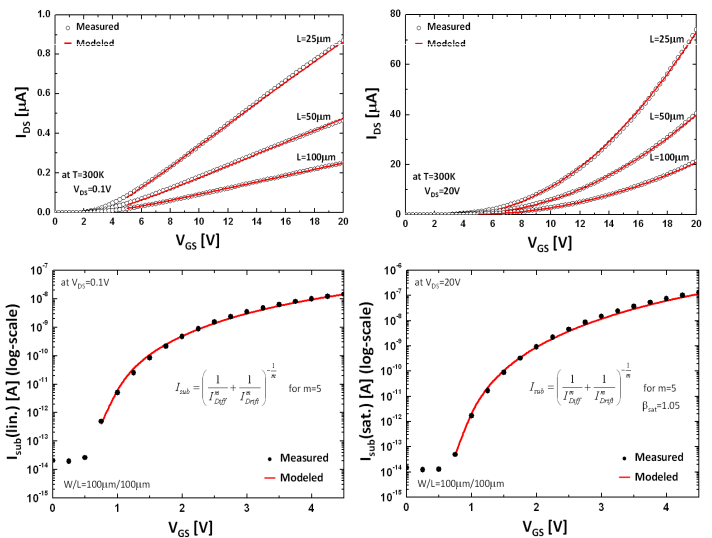
- Fully physical model developed for oxide TFTs, considering TLC and percolation mechanisms for above-threshold regime while considering both diffusion & drift transports for sub-threshold regime.

- Illustration of carrier transports:



Modes	$kT_i > kT$	$kT_i < kT$
Free Carrier (Boltzmann Approx.)	$n_{free}(E_F) = N_C \exp\left(\frac{E_F - E_m}{kT}\right)$	$n_{free}(E_F) = N_C \exp\left(\frac{E_F - E_m}{kT}\right)$
Trapped Carrier (Tail states)	$n_{tail}(E_F) \approx N_{tc}kT_i \exp\left(\frac{E_F - E_m}{kT_i}\right)$	$n_{tail}(E_F) \approx N_{tc}kT_i \exp\left(\frac{E_F - E_m}{kT}\right)$
$\gamma_{TLC} = \frac{n_{free}}{n_{free} + n_{tail}}$	$\approx \frac{N_C}{N_{tc}kT_i} \exp\left(E_F - E_m\right) \left(\frac{1}{kT} - \frac{1}{kT_i}\right)$	$= \frac{N_C}{N_C + N_{tc}kT_i}$

- Modeled results on I-V:



## Related Publications:

- Sungsik Lee *et al.*, *IEEE Journal of Display Technology* 9(11), 883 (2013).
- Sungsik Lee *et al.*, *SID Symposium Digest* 44(1), 22 (2013).